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PATENT & TRADEMARK OFFICE

AMENDMENT TRANSMITTAL LETTER

Docket No.
M4065.0166/P166-A
Art Unit
1765

Application No.
09/643,946

Filing Date
August 23, 2000

Examiner
L. Vinh

Applicant(s): Kevin J. Torek et al.

Invention: ACID BLEND FOR REMOVING ETCH RESIDUE

TO THE COMMISSIONER FOR PATENTS

Transmitted herewith is an Amendment Under 37 CFR 1.116 in the above-identified application.
The fee has been calculated as shown below.

| CLAIMS AS AMENDED | | | | | |
|--|----------------------------------|--------------------------------|-----------------------------|------|---|
| | Claims Remaining After Amendment | Highest Number Previously Paid | Number Extra Claims Present | Rate | |
| Total Claims | 19 | - 22 = | 0 | x | |
| Independent Claims | 3 | - 3 = | 0 | x | |
| Multiple Dependent Claims (check if applicable) <input type="checkbox"/> | | | | | |
| Other fee (please specify): | | | | | |
| TOTAL ADDITIONAL FEE FOR THIS AMENDMENT: | | | | | 0 |

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- ☒ Large Entity ☐ Small Entity
- ☒ No additional fee is required for this Amendment.
- ☐ Please charge Deposit Account No. _____ in the amount of \$ _____.
A duplicate copy of this sheet is enclosed.
- ☐ A check in the amount of \$ _____ to cover the filing fee is enclosed.
- ☒ The Commissioner is hereby authorized to charge and credit Deposit Account No. 04-1073 as described below.
- ☒ Credit any overpayment.
- ☒ Charge any additional filing or application processing fees required under 37 CFR 1.16 and 1.17.

MA D'Amico
~~Thomas J. D'Amico~~ **MARIC THRONON**
Attorney Reg. No.: ~~28,371~~ **33,082**

Dated: April 16, 2002

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Docket No.: M4065.0166/P166-A
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Kevin J. Torek et al.

Application No.: 09/643,946

Group Art Unit: 1765

Filed: August 23, 2000

Examiner: L. Vinh

For: ACID BLEND FOR REMOVING ETCH
RESIDUE

AMENDMENT UNDER 37 C.F.R. § 1.116

ATTN: Box AF
Commissioner for Patents
Washington, DC 20231

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Dear Sir:

In response to the final Office Action dated January 16, 2002 (Paper No. 7),
please amend the above-captioned application as follows:

In the Claims:

Replace claims 142, 150 and 158 with amended claims 142, 150 and 158 below.

500 →
✓
142. (Twice Amended) A conditioning solution for use in removing residues
remaining on a semiconductor substrate after a dry etch process, said conditioning solution
comprising:

hydrofluoric acid;

phosphoric acid;

propylene glycol and